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IBM Docket No. FIS920030147US1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: **Glenn Biery et al.**

Serial No.: **10/605,260** Date: **June 10, 2005**

Filed: **September 18, 2003** Group Art Unit: **2891**  
Batch No.:

Title: **TWO-MASK PROCESS FOR METAL-  
INSULATOR-METAL CAPACITORS AND SINGLE  
MASK PROCESS FOR THIN FILM RESISTORS** Examiner: **Igwe U. Anya**

**DeLIO & PETERSON, LLC**  
121 Whitney Avenue  
New Haven, CT 06510-1241

**LETTER TO OFFICIAL DRAFTSMAN**

**Mail Stop ISSUE FEE**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Applicants are herewith submitting **10** sheets of Formal Drawings for the approval of the Draftsman.

Please charge the Assignee IBM Corporation Deposit Account No. **09-0458** for any fee related to the acceptance of the attached Formal Drawings. A duplicate copy of this letter is enclosed for that purpose.

Respectfully submitted,

By: *Robert Curcio*

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